



# ***ECAL LONG SLAB R&D***

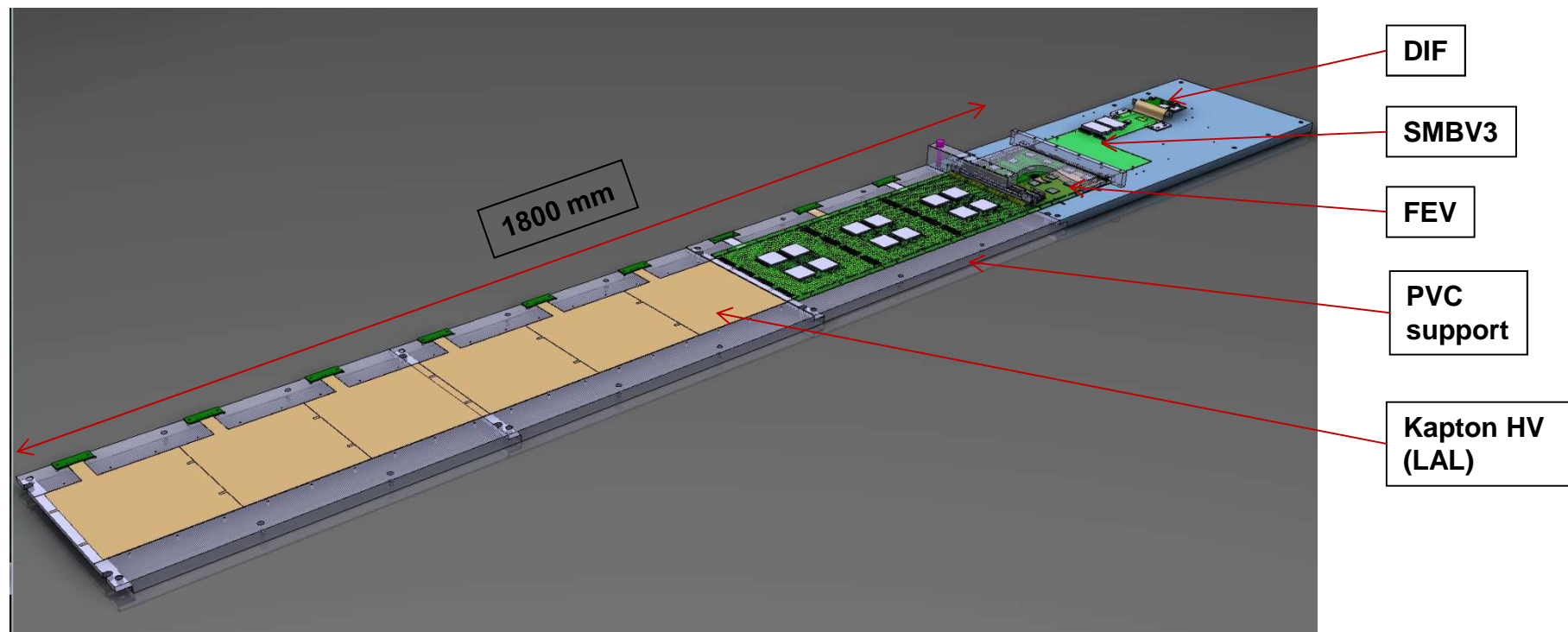
- 1 Long Slab setup « 10 ASU »
- 2 ASU Setup “4 wafers without glue”
- 3 Long asymmetrical H slab
- 4 Asymmetrical H Mould
- 5 Conclusion

# Long slab setup « 10 ASU »

⇒ The goal:

1.0 – inter-connection of 10 FEV

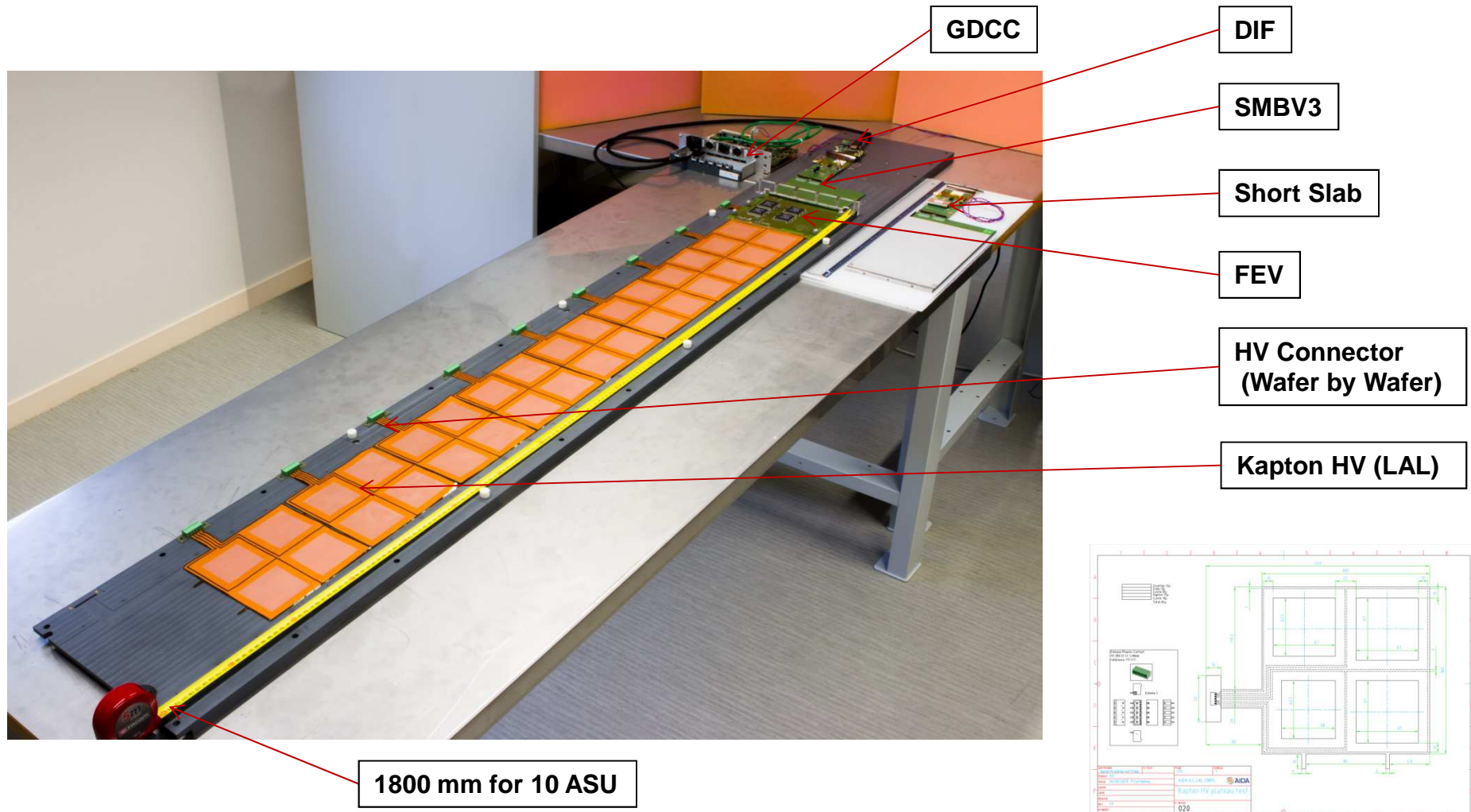
- Realize a test bench to verify inter-connections and data taking on 10 ASU
- Keep a possibility to easily disassemble it in order to move to a test beam



# Long slab setup « 10 ASU »

⇒ Our realization:

1.1 – inter-connection of 10 FEV

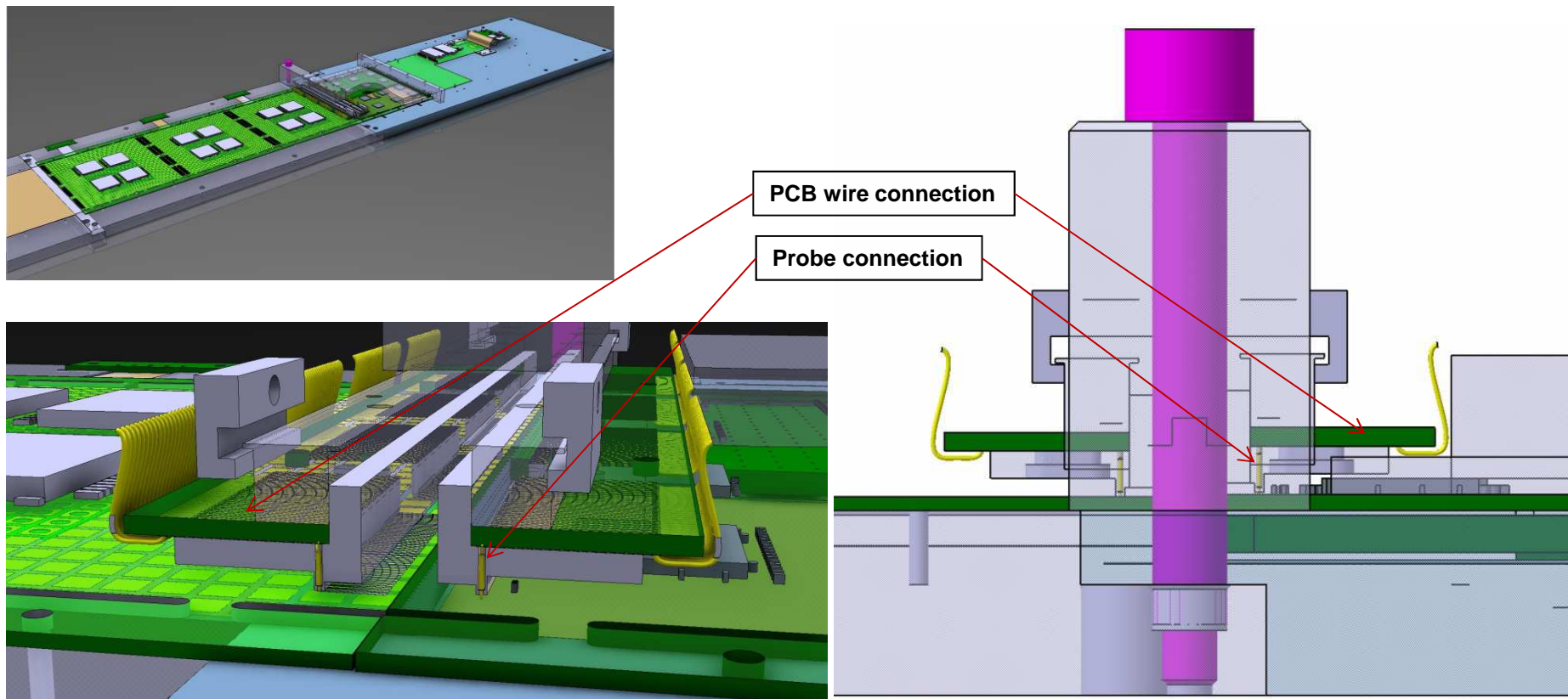


# Long slab setup « 10 ASU »

⇒ The goal:

## 1.2 – Temporary connection FEV 8 or 9

- Realize a system with temporary FEV interconnections in order to verify the data transfer

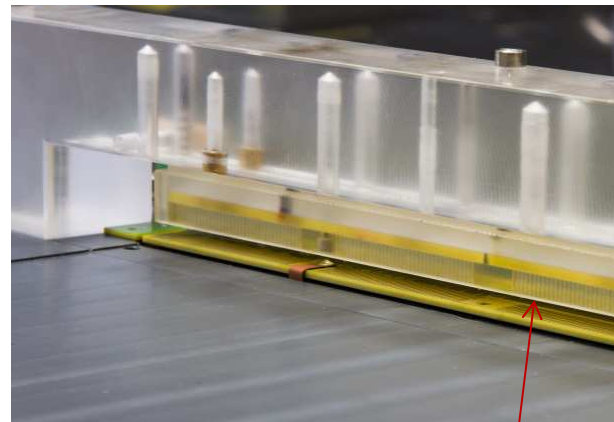
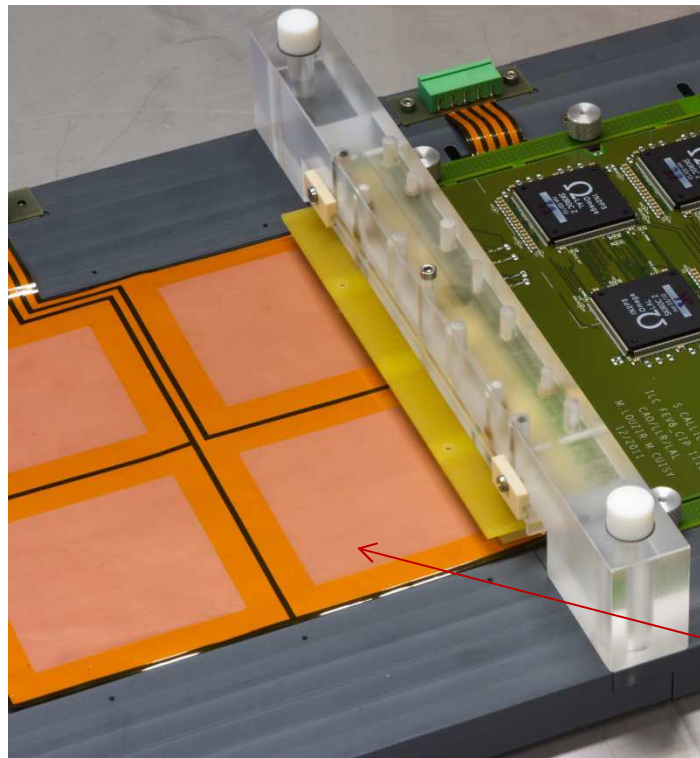




# Long slab setup « 10 ASU »

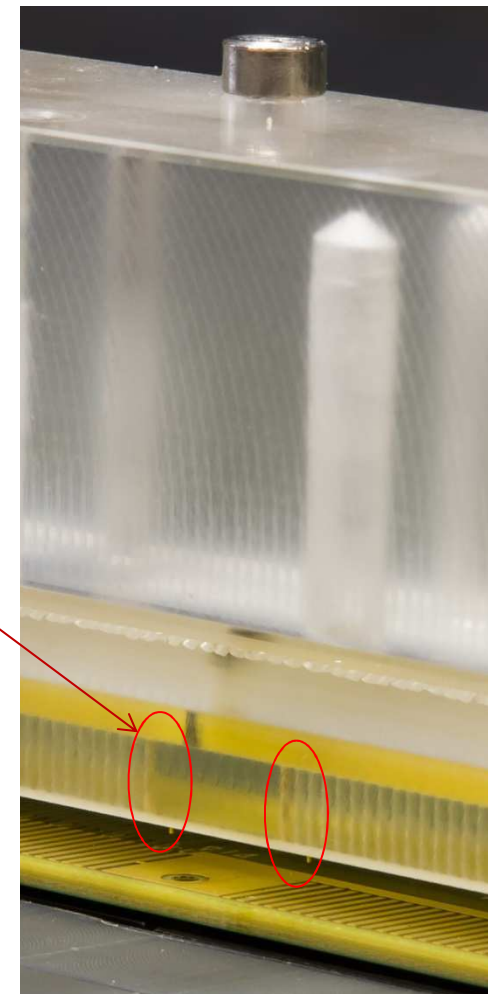
⇒ Our realization:

## 1.3 – Temporary connection of FEV 8 or 9



Mechanical support for Test Probes

HV Connector of LAL (Wafer by Wafer)

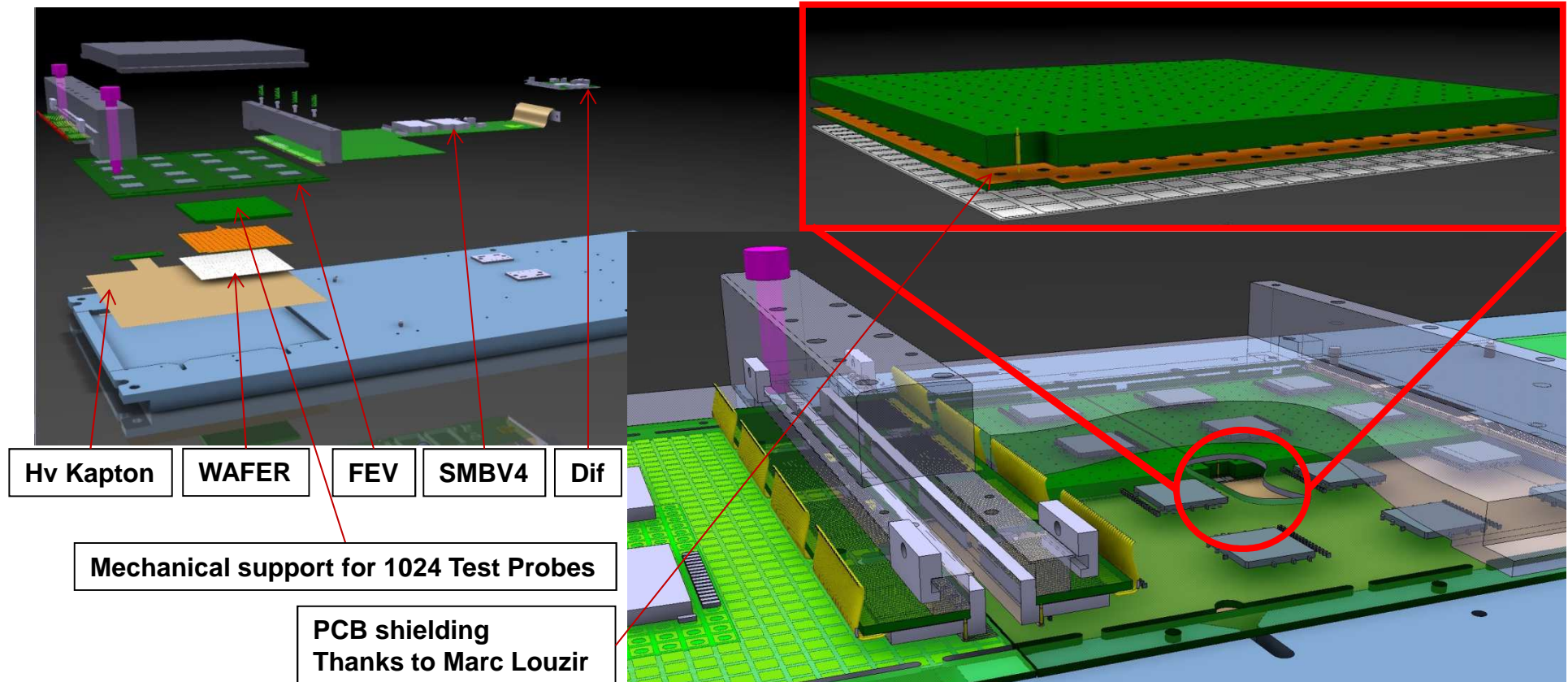


# ASU Setup “4 wafers without glue”

⇒ The goal:

2.0 – Setup option with support of test electric probes for connecting WAFER to FEV

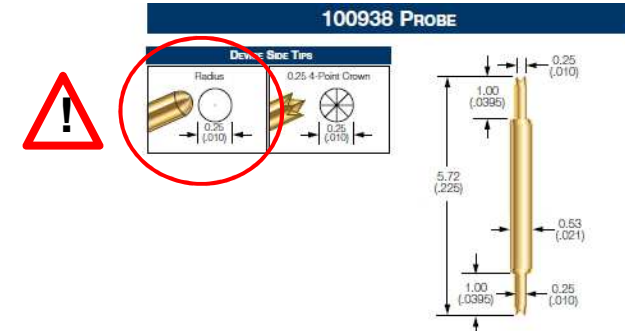
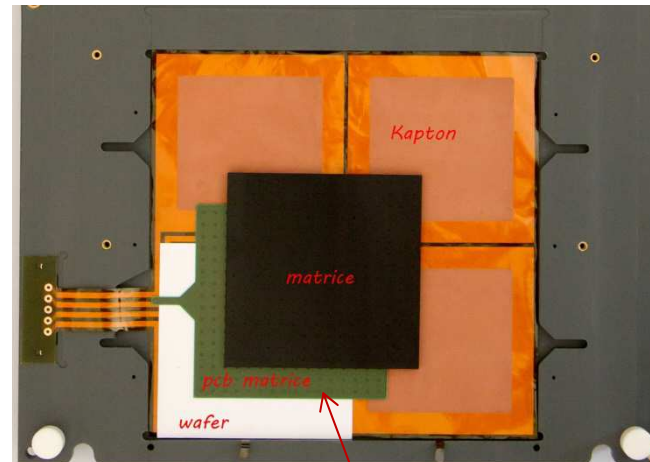
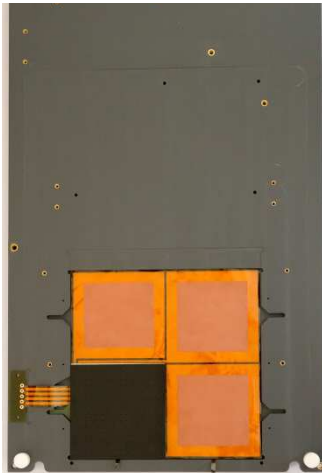
- Realize an assembly with removable wafer in order to acquire cosmic data. This assembly will test the entire acquisition chain (Wafer-FEV-SMBV4-DIF-GDCC-CCC-PC-Software) before the wafer gluing operation. The first test was realized last week



# ASU Setup “4 wafers without glue”

⇒ The goal:

## 2.1 – Setup option with support of test electric probes for connecting WAFER to FEV



### PROBE SPECIFICATIONS

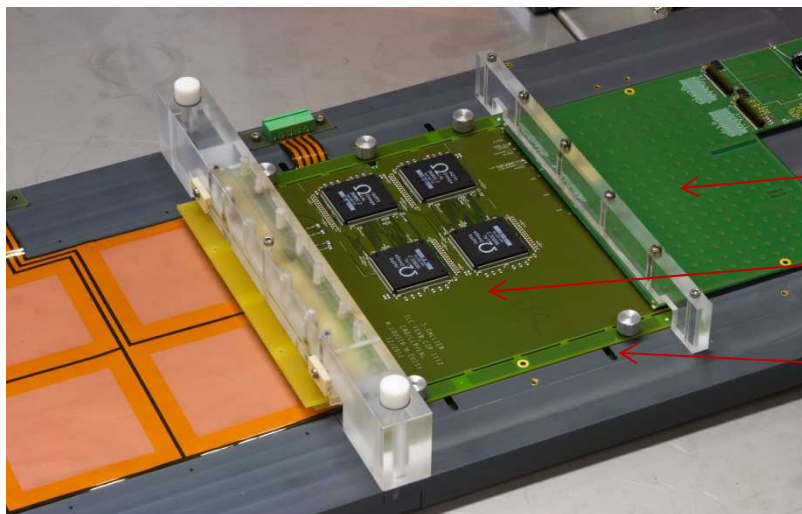
Minimum Device Pitch: 0.65mm (.026)  
 Signal Path Length: 4.75mm (.187)  
 Force per Contact: 31g (1.1oz.) @ 0.97mm (.038) travel  
 Device Compliance: 0.48mm (.019)  
 DUT Board Compliance: 0.48mm (.019)  
 Operating Temperature: -55°C to 150°C  
 Insertions: > 500,000

### MATERIALS

Barrel: Nickel/silver, gold plated  
 Spring: Stainless steel, gold plated  
 Device Side Contact: Full-hard beryllium copper, gold plated  
 Board Side Contact: Full-hard beryllium copper, gold plated

### ELECTRICAL SPECIFICATIONS

Typical Resistance: < 70 mΩ  
 Current Carrying Capacity: 3 amps continuous  
 (Current DC carry capability @ 80° C steady state)  
 Pattern 2a: R R R @ 0.65mm pitch  
 Characteristic Impedance: 50 Ω  
 Time Delay: 31 pSec  
 Loop Inductance: 1.46 nH @ 0.75mm pitch  
 Signal Pin to Return Capacitance: 0.10 pF  
 -1 dB Insertion Loss Bandwidth: > 2.4 GHz



PCB shielding  
 Thanks to Marc Louzir

SMBV4

FEV 8

Area PCB shielding  
 ground connection



# Long asymmetrical H slab

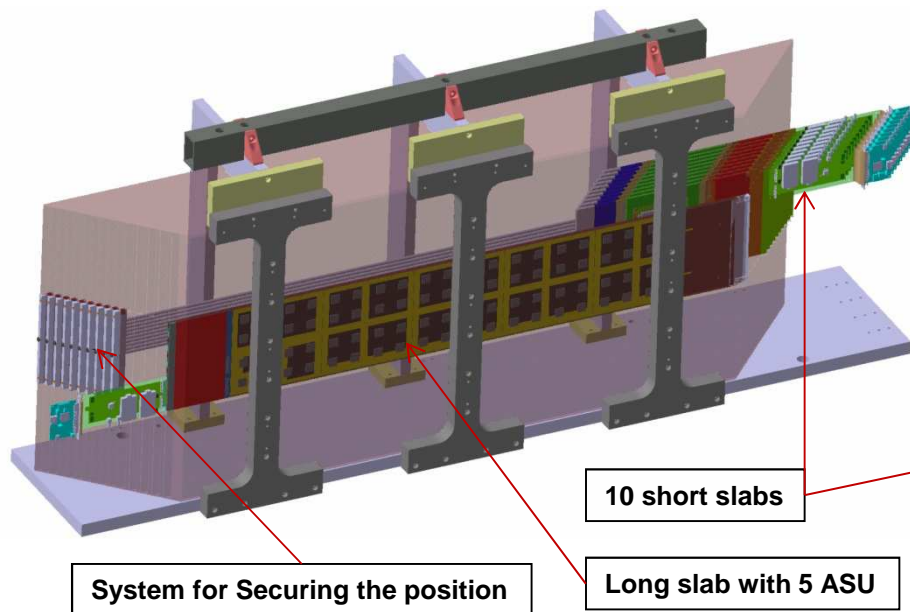
## ⇒ The goal:

*3.0 – Realized a long slab with H shape designed for the ECAL module. The setup intended for the future beam test is presented below. We have already a mechanical system for securing the position of the short slab (designed by Alain Bonnemaïson, LLR)*

- 10 short Slabs FEV9 or FEV8
- 1 long Slab FEV9 (5 ASU)

Future Ecal setup

present Ecal setup





# Long asymmetrical H slab

⇒ Ecal physical prototype

Ecal structure Design with 15 alveolars

## 3.1 – CURRENT THICKNESS

**A**  
 $4 \times 0,22 \text{ mm C} + 1 \times 15,3 \text{ mm C} + 3 \times 0,22 \text{ mm C} +$   
 $1 \times 0,1 \text{ mm epoxy} = \underline{16,94 \text{ mm}}$

**B**  
 $4 \times 0,22 \text{ mm C} + 1 \times 0,1 \text{ mm epoxy} + 1 \times 4,2 \text{ mm W} +$   
 $4 \times 0,22 \text{ mm C} + 1 \times 0,1 \text{ mm epoxy} = \underline{6,16 \text{ mm}}$

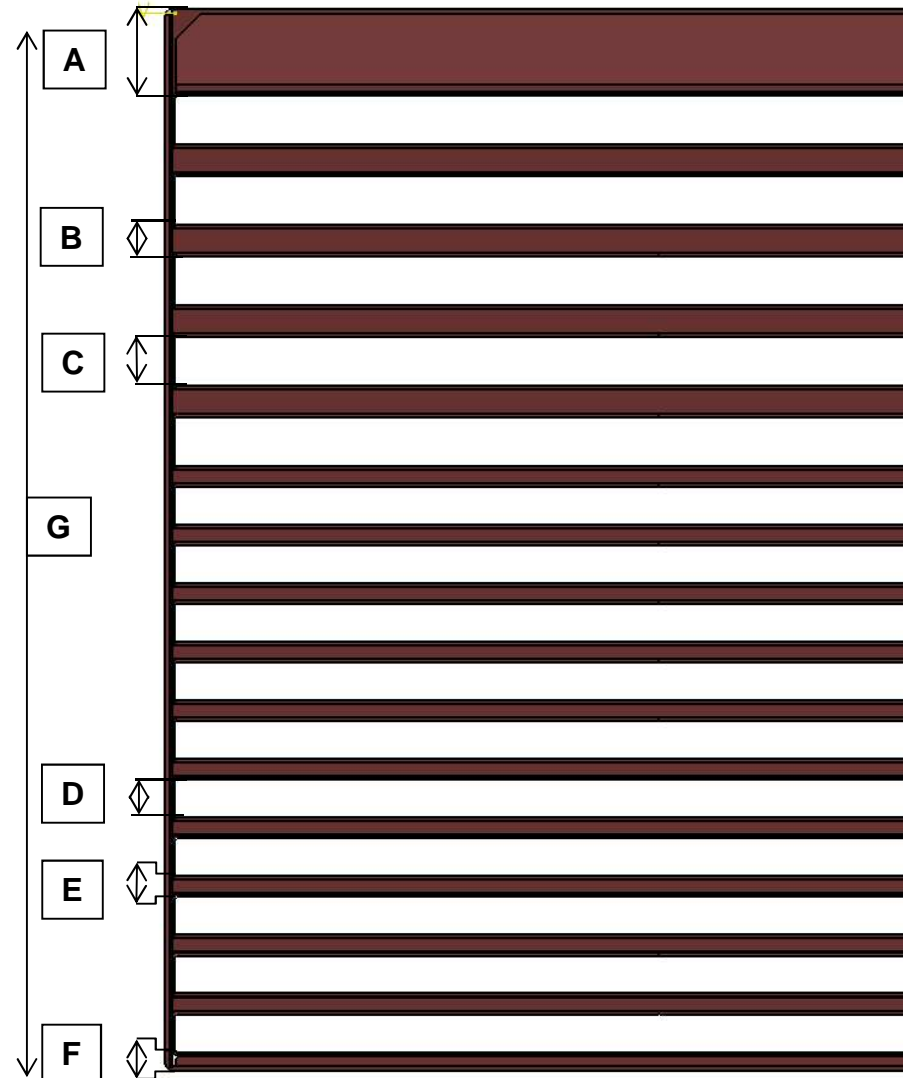
**C**  
 $\text{SLAB } 9,1 \text{ mm (with } 4,2 \text{ mm W)} +$   
 $0,3 \text{ mm gap} = \underline{9,4 \text{ mm}}$

**D**  
 $\text{SLAB } 7 \text{ mm (with } 2,1 \text{ mm W)} +$   
 $0,3 \text{ mm gap} = \underline{7,3 \text{ mm}}$

**E**  
 $4 \times 0,22 \text{ mm C} + 1 \times 0,1 \text{ mm epoxy} + 1 \times 2,1 \text{ mm W} +$   
 $4 \times 0,22 \text{ mm C} + 1 \times 0,1 \text{ mm epoxy} = \underline{4,06 \text{ mm}}$

**F**  
 $2 \times 0,22 \text{ mm C} + 1 \times 0,1 \text{ mm epoxy} + 1 \times 2 \text{ mm C} +$   
 $4 \times 0,22 \text{ mm C} + 1 \times 0,1 \text{ mm epoxy} = \underline{3,52 \text{ mm}}$

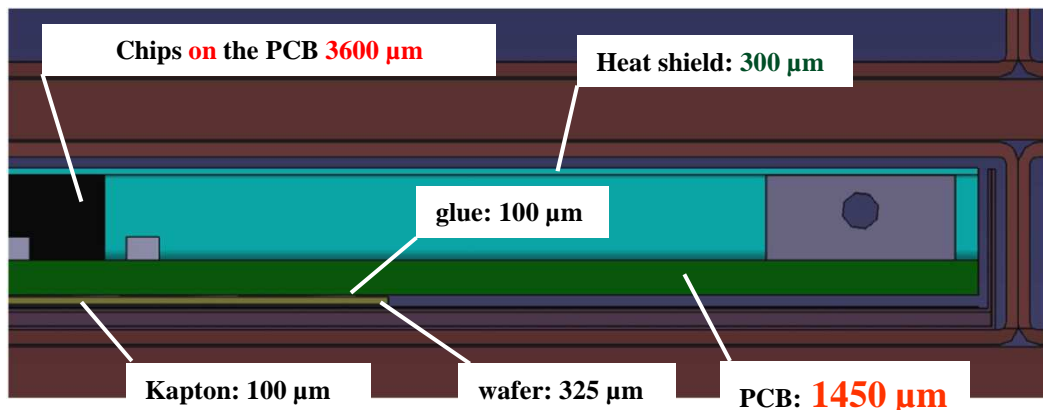
**G**  
 $16,94 \text{ mm} + 4 \times 6,16 \text{ mm} + 10 \times 9,4 \text{ mm} + 5 \times 9,4$   
 $+ 10 \times 7,3 + 3,52 = \underline{205,7 \text{ mm}}$



# Long asymmetrical H slab

## 3.2 – SLAB THICKNESS

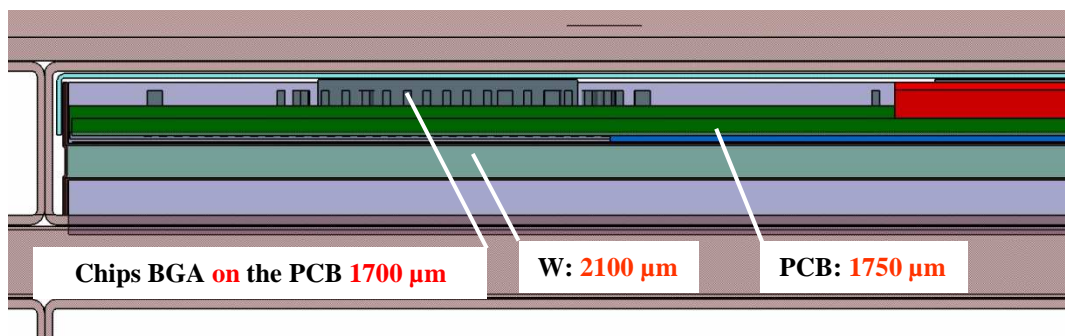
⇒ Conservative design: Short U Slab CIP, 1 SI detection layer per Slab



- ⇒ Gaps (slab integration) : 300 μm
- ⇒ Heat shield : 300 μm (LLR)
- ⇒ PCB : 1450 μm (flatness ok)
- ⇒ Chips : 3600 μm
- ⇒ Thickness of glue : 100 μm (LPNHE)
- ⇒ Thickness of wafer : 325 μm (LLR)
- ⇒ Thickness of glue : 100 μm (LAL)
- ⇒ Kapton® film HV : 100 μm (LAL)
- ⇒ Thickness of Carbon : 900 μm (LLR)
- ⇒ Thickness of scotch : 125 μm (LAL)
- ~~⇒ Thickness of W : 2100/4200 μm~~

⇒ Asymmetrical H design: 5 ASU detection on 1 layer per Long Slab

The expected slab thickness is 9,1 mm **if** :

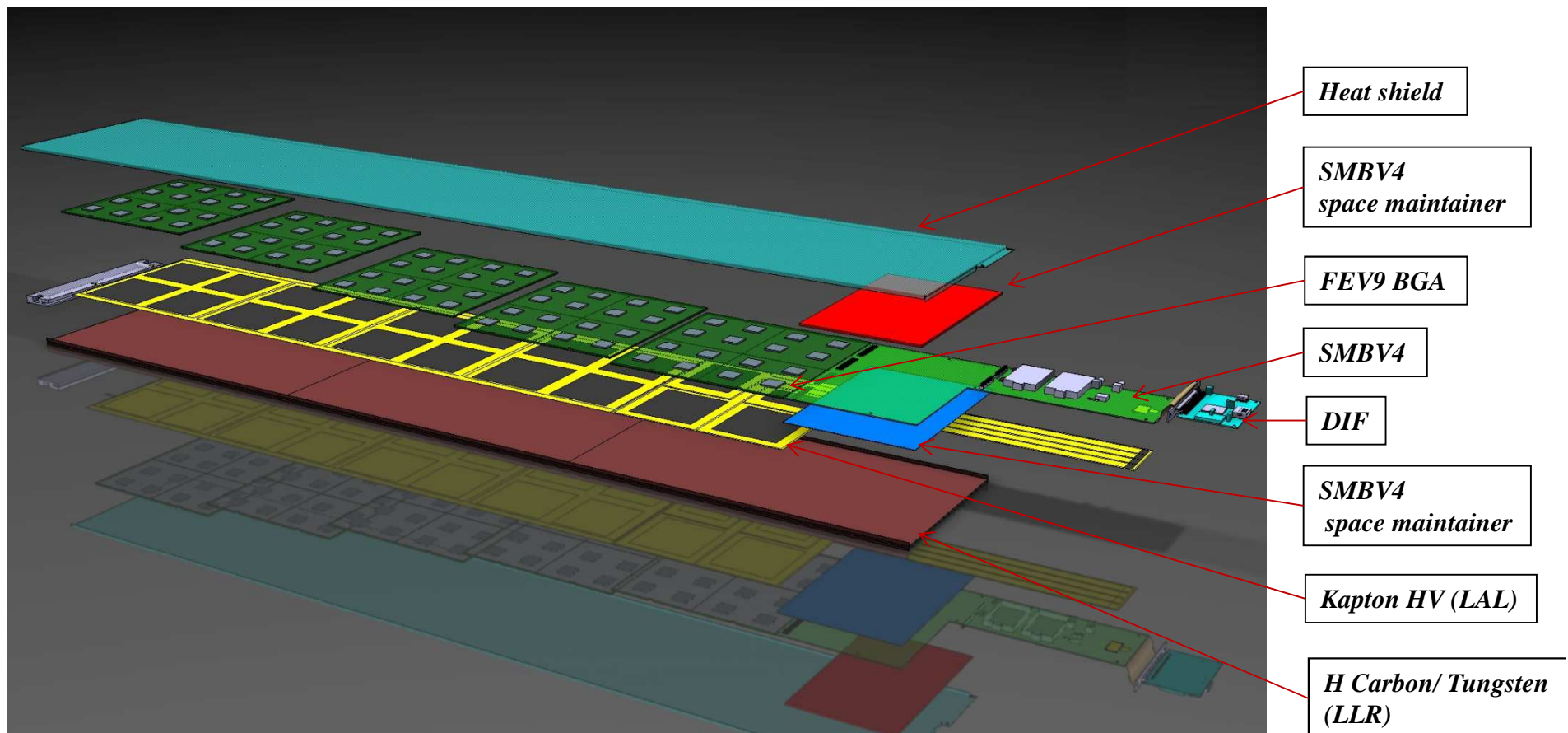


- ⇒ Gaps (slab integration) : 300 μm
- ⇒ Heat shield : 500 μm (LLR)
- ⇒ PCB : 1750 μm (flatness ok ?)
- ⇒ Chips BGA: 1700 μm
- ⇒ Thickness of glue : 100 μm (LPNHE)
- ⇒ Thickness of wafer : 325 μm (LLR)
- ⇒ Thickness of glue : 100 μm (LAL)
- ⇒ Kapton® film HV : 100 μm (LAL)
- ⇒ Thickness of W : 2100 μm

# Long asymmetrical H slab

⇒ Our design: “H slab with 5 FEV9 BGA”

## 3.3 – LONG SLAB component



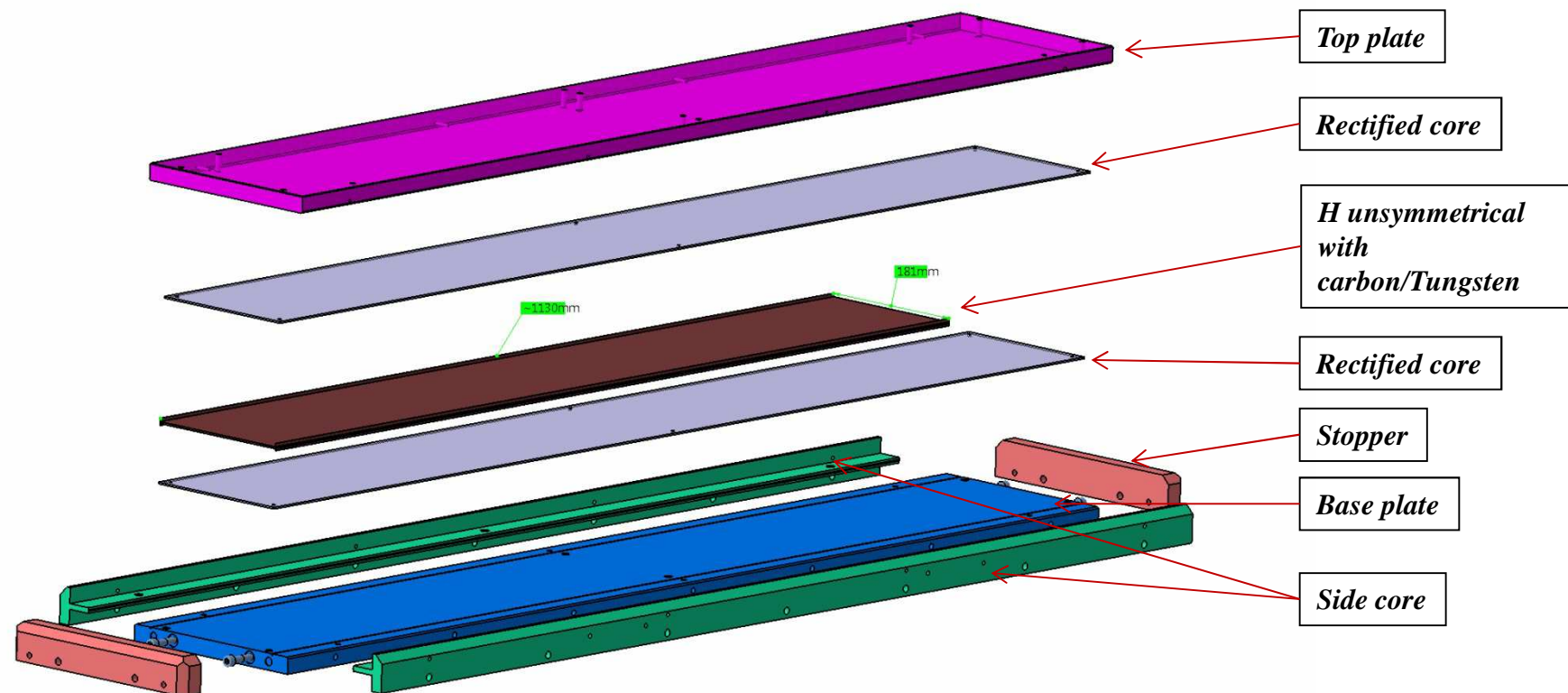


# asymmetrical H mould

⇒ Our design: “H slab with 5 FEV9 BGA”

4.0 – H mould will ensure :

- A flatness of  $\pm 0.05$  mm to 180mm
- Integration of 2.1 mm of tungsten within the H structure
- Compatibility with alveoli of 9.4 mm high and 182.3 mm long.



z  
y x

⇒ **Conclusion:**

**5.0 – Conclusion**

- *H Mould* → *The design will be completed by the end of September 2013*
- *H Long Slab* → *The first prototype will be moulded in the end of November 2013*
- *Long slab setup* → *The setup has just been assembled last week (07/09/2013)*
- *ASU setup* → *The setup has finish and the test has just started on 07/09/2013*

